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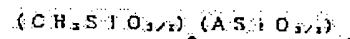
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(54) SPHERICAL POLYORGANOSILSESQUIOXANE FINE PARTICLE AND PRODUCTION THEREOF

(57)Abstract:

PURPOSE: To obtain the title fine particles useful for rubber, etc., having excellent lubricating properties, water repellence, mold release characteristics and improved stress relaxation by using a specific methyltrialkoxysilane and organotrialkoxysilane as a raw material.

CONSTITUTION: A raw material comprising a mixture of (A) at least one selected from a group consisting of a methyltrialkoxysilane shown by the formula  $\text{CH}_3\text{Si}(\text{OR})_3$  (R is 1-4C alkyl) and a partial hydrolyzate thereof and (B) at least one selected from a group consisting of an organotrialkoxysilane shown by the formula  $\text{ASi}(\text{OH})_3$  (Ar is amino, epoxy, vinyl or monofunctional organic group containing at least one of these functional groups) is hydrolyzed and condensed in an aqueous solution containing an alkali substance (e.g. alkali metal hydroxide) and then neutralized and dried to give fine particles shown by the formula  $[n/(m+n) \text{ is } 0.001-0.400 \text{ and } m \text{ and } n \text{ are positive integer}]$ .



## LEGAL STATUS

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